[WB2] Plasma Diagnostics and Process Monitoring Technology III

Date / Time: January 20 (Wed.), 2021 / 11:00-12:20
Place: Channel B
Session Chair(s): Duk Sun Han (KFE, Korea)

[WB2-1] Invited  11:00-11:30

Tomography-Based Optical Diagnostics for Real-Time Monitoring of Spatial Uniformity in Microelectronics Processing Plasmas

Wonho Choe
KAIST, Korea

[WB2-2]  11:30-11:50

Improvement of Triple Probe Measurement on Non-Maxwellian Plasmas

Namjae Bae, Jaemin Song, Jihoon Park, Haneul Lee, and Gon-Ho Kim
Seoul Nat’l Univ., Korea

[WB2-3] Invited  11:50-12:20

Predictive Control of the Plasma Processes after Discontinuities in the OLED Display Mass Production Line Referring to the PI-VM Model

Seolhye Park¹, Jaegu Seong¹, Yeongil Noh¹, Yoona Park¹, Yongsuk Jang¹, Taeyoung Cho¹, Jae Ho Yang¹, and Gon-Ho Kim²

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